

KINTEK SOLUTION

Mpcvd Catalog

Contact us for more catalogs of Sample Preparation, Thermal Equipment, Lab Consumables & Materials, Bio-Chem Equipment, etc...



KINTEK SOLUTION COMPANY PROFILE

>>> About Us

Kintek Solution Ltd is one technology orientated organization, team members are devoted to probing the most efficicent and reliable technology and innovations in the scienticfic researching equipment, fields like biochemical reacting, new materials researching, heat treatment, vaccum creating, refrigerating, as while as pharmaceutical and petroleum extracting equipment.

In the past 20 years, we earned rich experiences in this researing equipment field, we are capable to supply both the equipment and solution according to customer's needs and realities, we have also developed lots of customer tailer equipment accoding to a specific working purpose, and we have lots of successful projects in many universities and institutes from different countries, like Asia,Europe,North and south America, Australia and New Zealand, middle east, and Africa.

Profession, quick response, hard working, and sincerity is a remarkable label of our team meambers working attitude, which earn us a sound reputation among our clients.

We are here and ready to service our clients from different countries and regions, and share the most efficent and reliable technology together!





Cylindrical Resonator Mpcvd Diamond Machine For Lab Diamond Growth

Item Number: KTWB315



Introduction

Learn about Cylindrical Resonator MPCVD Machine, the microwave plasma chemical vapor deposition method used for growing diamond gemstones and films in the jewelry and semiconductor industries. Discover its cost-effective advantages over traditional HPHT methods.

Microwave system	 Microwave frequency 2450±15MHZ, Output power 1[]10 KW continuously adjustable Microwave output power stability: Microwave leakage ≤2MW/cm2 Output wave guide interface: WR340, 430 with FD-340, 430 standard flange Cooling water flow: 6-12L/min System standing wave coefficient: VSWR ≤ 1.5 Microwave manual 3 pin adjuster, excitation cavity, high-power load Input power supply: 380VAC/50Hz ± 10%, three-phase
Reaction chamber	 Vacuum leakage rate The limit pressure is less than 0.7 Pa(Standard setup with Pirani vacuum gauge) The pressure rise of chamber shall not exceed 50Pa after 12 hours of pressure maintaining Working mode of reaction chamber: TM021 or TM023 mode Cavity type: Cylindrical resonant cavity, with maximum bearing power of 10KW, made of 304 stainless steel, with water-cooled inter-layer, and high purity quartz plate sealing method. Air intake mode: Top annular uniform air intake Vacuum sealing: The bottom connection of the main chamber and the injection door are sealed with rubber rings, the vacuum pump and bellows are sealed with KF, the quartz plate is sealed with a metal C-ring, and the rest are sealed with CF Observation and temperature measurement window: 8 observation port Sample load port in front of chamber Stable discharge within the pressure range of 0.7KPa~30KPa (the power pressure shall be matched)
Sample holder	 Diameter of sample table≥72mm, effective use area≥66 mm Base plate platform water-cooled sandwich structure Sample holder can be lifted and lowered evenly electrically in the cavity
Gas flow system	 All metal welding air disk Welding or VCR joints shall be used for all internal gas circuits of the equipment. 5 channels MFC flow meter, H2/CH4/O2/N/Ar. H2: 1000 sccm; CH4:100 sccm; O2: 2 sccm; N2: 2 sccm; Ar: 10 sccm Working press 0.05-0.3MPa, accuracy ±2% Independent Pneumatic valve control for each channel flow meter
Cooling system	 3 lines water cooling, real-time monitoring of temperature and flow. The system cooling water flow is ≤ 50L/min The cooling water pressure is
Temperature sensor	 The external infrared thermometer has a temperature range of 300-1400 °C Temperature control accuracy



Control system

• Siemens smart 200 PLC and touch screen control are adopted.

- The system has a variety of programs, which can realize the automatic balance of growth temperature, accurate control of growth air pressure, automatic temperature rise, automatic temperature drop and other functions.
- The stable operation of the equipment and comprehensive protection of the equipment can be achieved through the monitoring of water flow, temperature, pressure and other parameters, and the reliability and safety of the operation can be guaranteed through functional interlocking.

Optional function Center monitoring system

Substrate basing power



Bell-Jar Resonator Mpcvd Diamond Machine For Lab And Diamond Growth

Item Number: KTMP315



Introduction

Get high-quality diamond films with our Bell-jar Resonator MPCVD machine designed for lab and diamond growth. Discover how Microwave Plasma Chemical Vapor Deposition works for growing diamonds using carbon gas and plasma.

Microwave system	 Microwave frequency 2450±15MHZ, Output power 1□10 KW continuously adjustable Microwave output power stability: Microwave leakage ≤2MW/cm2 Output wave guide interface: WR340, 430 with FD-340, 430 standard flange Cooling water flow: 6-12L/min System standing wave coefficient: VSWR ≤ 1.5 Microwave manual 3 pin adjuster, excitation cavity, high-power load Input power supply: 380VAC/50Hz ± 10%, three-phase
Reaction chamber	 Vacuum leakage rate The limit pressure is less than 0.7 Pa(Standard setup with Pirani vacuum gauge) The pressure rise of chamber shall not exceed 50Pa after 12 hours of pressure maintaining Working mode of reaction chamber: TM021 or TM023 mode Cavity type: Butterfly resonant cavity, with maximum bearing power of 10KW, made of 304 stainless steel, with water-cooled inter-layer, and high purity quartz plate sealing method. Air intake mode: Top annular uniform air intake Vacuum sealing: The bottom connection of the main chamber and the injection door are sealed with rubber rings, the vacuum pump and bellows are sealed with KF, the quartz plate is sealed with a metal C-ring, and the rest are sealed with CF Observation and temperature measurement window: 4 observation ports Sample load port in front of chamber Stable discharge within the pressure range of 0.7KPa~30KPa (the power pressure shall be matched)
Sample holder	 Diameter of sample table≥70mm, effective use area≥64 mm Base plate platform water-cooled sandwich structure Sample holder can be lifted and lowered evenly electrically in the cavity
Gas flow system	 All metal welding air disk Welding or VCR joints shall be used for all internal gas circuits of the equipment. 5 channels MFC flow meter, H2/CH4/O2/N/Ar. H2: 1000 sccm; CH4:100 sccm; O2: 2 sccm; N2: 2 sccm; Ar: 10 sccm Working press 0.05-0.3MPa, accuracy ±2% Independent Pneumatic valve control for each channel flow meter
Cooling system	 3 lines water cooling, real-time monitoring of temperature and flow. The system cooling water flow is ≤ 50L/min The cooling water pressure is
Temperature sensor	 The external infrared thermometer has a temperature range of 300-1400 °C Temperature control accuracy



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Optional function Center monitoring system

Substrate basing power



Drawing Die Nano-Diamond Coating Hfcvd Equipment

Item Number: MP-CVD-100



Introduction

The nano-diamond composite coating drawing die uses cemented carbide (WC-Co) as the substrate, and uses the chemical vapor phase method (CVD method for short) to coat the conventional diamond and nano-diamond composite coating on the surface of the inner hole of the mold.

Learn More

Comparation table between traditional and nano diamond coated drawing die

HFCVD technical composition			
Technical Parameters	Equipment composition	System Configuration	
Bell Jar: Dia. 500mm, Height 550mm, SUS304 stainless steel chamber; inner stainless steel skin insulation, lifting height is 350mm;	A set of vacuum chamber (bell jar) main body (jacketed water-cooling structure)	Vacuum chamber (bell jar) main body;The cavity is made of high-quality 304 stainless steel; Vertical bell jar: the jacketed water-cooling jacket is installed on the overall periphery of the bell jar. The inner wall of the bell jar is insulated with stainless steel skin, and the bell jar is fixed on the side . Accurate and stable positioning ; Observation window: horizontally arranged in the middle of the vacuum chamber 200mm Observation window, water cooling, baffle, side and upper configuration 45 Degree bevel angle, 50° observation window (observe the same point as the horizontal observation window, and the sample supporting platform); the two observation windows maintain the existing position and size.Bell jar bottom is 20mm higher than the plane of the bench , set cooling; the holes reserved on the plane, such as large valves, air release valves, air pressure measurement, bypass valves, etc., are sealed with metal mesh and reserved for installing electrodes Interface;	
Equipment table: L1550* W900*H1100mm	One set of drag sample table device (adopting double- axis drive)	Sample holder device: Stainless steel sample holder (welding water cooling) 6- position device; it can be adjusted separately, only up and down adjustment, the up and down adjustment range is 25mm, and the left and right shaking is required to be less than 3% when going up and down (that is, the left and right shaking of rising or falling by 1mm is less than 0.03mm), and the sample stage does not rotate when rising or falling.	
Ultimate vacuum degree: 2.0×10- 1Pa ;	A set of vacuum system	Vacuum system: Vacuum system configuration: mechanical pump + vacuum valve + physical bleed valve + main exhaust pipe + bypass; (provided by the vacuum pump supplier), the vacuum valve uses a pneumatic valve; Vacuum system measurement: Membrane pressure.	
Pressure rise rate : ≤5Pa/h;	Two channels mass flow meter gas supply system	Gas supply system: The mass flow meter is configured by Party B, two-way air intake, the flow rate is controlled by the mass flow meter, after the two-way meeting, it enters the vacuum chamber from the top , and the inside of the air intake pipe is 50mm	
Sample table movement: up and down range is \pm 25m; it is required to shake left and right ratio when up and down by \pm 3%;	One set of electrode device (2 channels)	Electrode device: The length direction of the four electrode holes is parallel to the length direction of the support platform, and the length direction is facing the main observation window with a diameter of 200mm .	
Working pressure: use membrane gauge pressure gauge, measuring range: 0 ~ 10kPa; work constant at 1kPa ~5kPa,the constant pressure value changes plus or minus 0.1kPa;	A set of cooling water system	Cooling water system: The bell jar, electrodes, and bottom plate are all equipped with circulating water cooling pipelines, and are equipped with insufficient water flow alarm device 3.7: control system. Switches, instruments, instruments and power supply for bell lifting, deflation, vacuum pump, main road, bypass, alarm, flow, air press etc. are set on the side of the stand, and are controlled by a 14 -inch touch screen; the equipment has a fully automatic control program without manual intervention, and can store data and call data	
Air intake position: air intake at the top of the bell jar, and the position of the exhaust port is located directly below the sample holder;	Control system		



Control System: PLC controller + 10-inch touch screen	A set of automatic pressure control system (original pressure control valve imported from Germany)	
Inflation system: 2 channels mass flow meter, flow range: 0- 2000sccm and 0-200sccm; Pneumatic valve valve	Resistance Vacuum Gauge	
3.1.10 Vacuum pump: D16C vacuum pump		
Technical indicators	Traditional drawing die	
Coating Surface Grain Size	none	
Coating diamond content	none	
Diamond Coating Thickness	none	
Surface roughness	Ra≤0.1mm	
Coating drawing die inner hole diameter range	Φ3 ~ Φ70mm	
Service life span	Life span depends on working conditions	
Surface friction coefficient	0.8	



915Mhz Mpcvd Diamond Machine

Item Number: MP-CVD-101



Introduction

915MHz MPCVD Diamond Machine and its multicrystal effective growth, the maximum area can reach 8 inches, the maximum effective growth area of single crystal can reach 5 inches. This equipment is mainly used for the production of large-size polycrystalline diamond films, the growth of long single crystal diamonds, the lowtemperature growth of high-quality graphene, and other materials that require energy provided by microwave plasma for growth.



1	Microwave power supply	Standard domestic magnetron: Yingjie Electric / Distinguish power supply Domestic solid-state source: Watson (+30,000) Imported magnetron: MKS/ pastoral (+100, 000)
2	Waveguide, three pins, mode converter, upper resonator	Self made
3	Vacuum reaction chamber (upper chamber, lower chamber, connectors)	Self made
4	Infrared thermometers, optical displacement components, brackets	Infrared thermometers, optical displacement components, Fuji Gold Siemens + Schneider brackets
5	Water-cooling table motion components (cylinders, workpieces, etc.)	
6	Ceramic thin film vacuum gauge,Pirani vacuum gauge	Inficon
7	Vacuum valve components (ultra-high vacuum gate valve, precision pneumatic valve*2, electromagnetic vacuum charging differential valve)	Fujikin + Zhongke + Himat
8	Vacuum pump and connecting pipe fittings, tee, KF25 bellows*2, adapter	Pump: Flyover 16L
9	Metal microwave sealing ring*2; metal vacuum sealing ring*1; Quartz plate	Quartz: Shanghai FeilihuaSemiconductor Grade High Purity Quartz
10	Circulating water components (joints, diverter blocks, flow detectors)	Japanese SMC/CKD
11	Pneumatic part (CKD filter, airtac multi-way solenoid valve, pipe fittings and adapters	5)
12	Gas connector, EP gas pipe, VCR connector, filter $0.0023 \mu m$ *1, filter $10 \mu m$ *2	Fujikin
13	Machine casing, stainless steel table, universal wheels, feet, bracket fastening screws, etc	custom processing
14	Gas flow meter*6 (including one pressure control)	Standard seven-star , optional Fuji Gold (+34,000) / Alicat (42,000)
15	Gas plate processing (5-way gas, filter*5, pneumatic valve*5, manual valve*6, pipeline welding)	Fuji Gold
16	PLC automatic control	Siemens + Schneider
17	Molybdenum table	



High Precision Diamond Wire Cutting Machine

Item Number: CM-1



Introduction

The high precision diamond wire cutting machine is a versatile and precise cutting tool designed specifically for material researchers. It utilizes a continuous diamond wire cutting mechanism, enabling precise cutting of brittle materials such as ceramics, crystals, glass, metals, rocks, and various other materials.

Power supply voltage	220V 50Hz; Maximum power:
Spindle speed	Adjustable within 2rpm to 260rpm
Control system	Manual control: Y axis and Z axis speed range 1 40mm/min; Automatic control: Y axis feed length 0.01 50mm; Z axis feed speed 0.05mm 40mm/min length 0.01 50mm; Z axis feed speed 0.05mm 40mm/min Z axis feed length 1 60mm; Automatic cutting frequency 1 99;
Total length of cutting line	20m
Inner distance between two guide wheels	95mm
Y-axis travel	≤ 50mm
Z-axis travel	≤ 60mm
2D fixture	Horizontal rotation 0-360 °, left and right inclination 20°
Load plate size	80mm× 51mm
Cutting depth	≤ 50mm 11. Maximum sample size for cutting: Ø 50mm × 50mm



Workbench 800Mm * 800Mm Diamond Single Wire Circular Small Cutting Machine

Item Number: CM-2



Introduction

Diamond wire cutting machines are mainly used for precision cutting of ceramics, crystals, glass, metals, rocks, thermoelectric materials, infrared optical materials, composite materials, biomedical materials and other material analysis samples. Especially suitable for precision cutting of ultra-thin plates with thickness up to 0.2mm.

Wire winding drum motor parameters	AC220v 50Hz 300
Linear speed	0-8m/s
Total length of cutting line	150m
Sample weight (max)	Зkg
Z-axis stroke	≤ 160mm
Y-axis stroke	≤ 180mm
Cutting sample diameter (max)	Φ 150 mm
Tensioning structure	Pneumatic tensioning
Tension adjustment range	0.1-0.4MPa
Diamond wire diameter	
Size	617x620x1500mm
Weight	183kg



12 Inch/24 Inch High Precision Automatic Diamond Wire Cutting Machine

Item Number: CM-3



Introduction

The high precision automatic diamond wire cutting machine is a versatile cutting tool that uses a diamond wire to cut through a wide range of materials, including conductive and non-conductive materials, ceramics, glass, rocks, gems, jade, meteorites, monocrystalline silicon, silicon carbide, polycrystalline silicon, refractory bricks, epoxy boards, and ferrite bodies. It is especially suitable for cutting various brittle crystals with high hardness, high value, and easy to break.

Power supply	220V 50Hz	
Power		
Spindle motor	AC variable frequency motor, power 250W	
Y, Z, R-axis motors	precision stepper motors	
Cutting line wire transportation speed	0-8m/s adjustable,digital display	
Total length of cutting line	≤ 150m	
Cutting line diamete	≤ 0.45mm	
Y-axis travel	≤ 300mm, digital display	
Z-axis travel	≤ 300mm, digital display	
Y and Z axis feed indication accuracy	0.01mm	
Workbench corner	0-360 ° Resolution 0.01 ° Digital display	
Workbench repeat positioning accuracy		
Cutting sample size	Ø 300mm × 300mm (max)	





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